

## ***UHV Technologies, Inc. introduces long life nano-crystalline diamond like carbon (n-DLC) stripper foils***

- \* Developed in collaboration with TRIUMF, BC, Canada\*\*
- \* Proprietary (patent pending) technology
- \* Recent funding from US Department of Energy\*\*\*
- \* Free-standing and Frame mounted foils are available
- \* Thicknesses as large as 5 um (1000 ug/cm<sup>2</sup>)



\*

### Available Thin Film Services

- \* 10,000 sq.ft. thin film R&D facility
- \* Metal films and coatings on substrates
- \* Free-standing metal foils
- \* Nano-Diamond and DLC films
- \* Transparent conductor thin films
- \* Oxide and nitride coatings
- \* Wire and fiber coatings
- \* AR and optical coatings

### Other Products

- \* Thin Film Equipment
- \* Process Control Electronics
- \* High Tech Product Prototyping
- \* Aligned Carbon Nanotubes
- \* Metal Nanoelectrodes
- \* Evaporation Shadow Masks
- \* Computer Automation
- \* High Throughput Microarray Equipment

\*\* <http://www.triumf.info/public/repository/ttb/ttb200605.pdf>

### In-House Processes

- \* Pulsed Laser Deposition (PLD)
- \* Plasma Enhanced CVD (PECVD)
- \* Hot Filament PECVD
- \* DC and RF Multi-Source Bias Sputtering
- \* Plasma and Reactive Ion Etching (RIE)
- \* Ion Beam Deposition (IBD)
- \* Carbon Arc, E-beam and Thermal Evaporation

### Equipment for Sale

- \* Pulsed Laser Deposition (PLD-1000)
- \* Nanotechnology R&D (Nano-100)
- \* Plasma Enhanced CVD (Nano-100P)
- \* Hot Filament PECVD (Nano-100HF)
- \* DC and RF Multi-Source Bias Sputtering
- \* Plasma and Reactive Ion Etching (RIE)
- \* Ion Beam Deposition (IBD)
- \* Carbon Arc, E-Beam and Thermal Evaporation

\*\*\* [http://www.science.doe.gov/sbir/awards\\_abstracts/sbirstr/cycle24/phase1/](http://www.science.doe.gov/sbir/awards_abstracts/sbirstr/cycle24/phase1/)